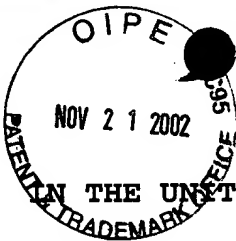


SON-2192



#5/Pre-AMTA
12/4/02
J.R.
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Koji KIKUCHI

Examiner:

Application No. 09/939,773

Art Unit: 2812

Filed: August 28, 2001

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For: MANUFACTURING METHOD OF A PHASE-SHIFT MASK, METHOD OF FORMING A RESIST PATTERN AND MANUFACTURING METHOD OF A SEMICONDUCTOR DEVICE

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, DC 20231

Sir:

Prior to examination on the merits, please amend the above-identified application as follows:

IN THE TITLE:

Please change the title to --MANUFACTURING METHOD OF A PHASE-SHIFT MASK, METHOD OF FORMING A RESIST PATTERN AND MANUFACTURING METHOD OF A SEMICONDUCTOR DEVICE--

IN THE SPECIFICATION:

Please amend the application by entering the enclosed substitute specification in place of that which was previously filed. A red-lined copy of the specification is also attached incorporating the changes.

IN THE CLAIMS:

Please amend claims 1-15 as set forth below in clean form. Additionally, in accordance with 37 CFR 1.121(c)(1)(ii), amended claim(s) is/are set forth in a marked-up version in the page(s)